

Single crystalline β -FeSi₂ grown using high-purity FeSi₂ source

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Abstract

We have investigated the effect of FeSi₂ source purity on the electrical property of β -FeSi₂ grown from solution. A high-purity FeSi₂ source avoided a contamination of Cu and W metals was synthesized by melting a high-purity Fe (5N) and Si (5N-up) in a quartz ampoule. Glow discharge mass spectrometry revealed that the purity of the FeSi₂ source synthesized using 5N-Fe and a quartz-ampoule-melting process is one order of magnitude higher than that of the conventional arc-melted FeSi₂ source using 4N-Fe. The β -FeSi₂ crystals grown using the high-purity FeSi₂ and Zn solvent showed n-type conduction, whereas those grown using the arc-melted FeSi₂ showed p-type. The carrier concentration of the n-type crystals was $(4.9\text{--}6.3) \times 10^{18} \text{ cm}^{-3}$, which was more than 10 times higher than that of the p-type crystals ($5.2 \times 10^{17} \text{ cm}^{-3}$). From the ICP-MS and SIMS analysis of the grown crystals, we found that dominant impurity concentrations (Cr, Mn, Co, Ni, Cu, Zn and W) in the p-type crystals were higher than those in the n-type ones. Therefore, the p-type conductivity of undoped crystals grown using Zn solvent results from unintentional doping by the high impurity level of the used FeSi₂ source.

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1. Introduction

Semiconducting iron disilicide, β -FeSi₂, has been attracting much attention in recent years because of its technological potential in the field of optoelectronic and thermoelectric applications [1]. Since the successful electroluminescence (EL) from β -FeSi₂/Si structure [2], a lot of researchers have investigated the optical properties of β -FeSi₂ to clarify the luminescence mechanism [3–8]. However, the luminescence mechanism has not been clearly understood, so far.

One of the interesting facts is that most of luminescence is observed from thin film or precipitate β -FeSi₂ [9,10]. Recently, Udono et al. observed the photoluminescence from solution grown β -FeSi₂, but the intensity is very weak [11]. In order to progress the understanding of the luminescence mechanism of β -FeSi₂, it is necessary to prepare bulk β -FeSi₂ single crystal with high-crystalline quality and high purity.

A purity of iron source is significant issue for the crystal growth of β -FeSi₂ because metal impurity in Fe source affects the electrical property of the crystal. Heinrich et al. and Behr et al. reported that the conduction type of chemical vapor transport (CVT) grown crystal changes from p-to n-type when the Fe source changes from 4N- to 5N-grade [12,13]. In the solution growth using Zn solvent and 4N-grade Fe source, p-type crystal ($p \sim 4 \times 10^{17} \text{ cm}^{-3}$) is usually grown [14]. However, the origin of its p-type carrier is not clearly understood, so far. In this paper, we report the synthesis of high-purity FeSi₂ alloy source and the solution growth of β -FeSi₂ using Zn (6N) solvent and the synthesized high-purity FeSi₂ source.

2. Experimental

A high-purity FeSi₂ alloy ingot was synthesized from the melt using a silicon furnace. A certain amount of silicon (5Nup) and iron (5N) [15] was enclosed in a purified quartz ampoule under a high vacuum ($<5 \times 10^{-6}$ Torr). The ampoule was heated at 1350 °C for 10 min and then cooled. The composition ratio of Si/Fe was changed between 1.5 and 2.5 to

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examine the influence of the source composition on the electrical properties of β -FeSi₂. Concentration of impurities in the synthesized FeSi₂ ingot was analyzed by induced coupled plasma mass spectrometry (ICP-MS) and glow discharge mass spectrometry (GDMS). We also measured an arc-melted FeSi₂ source, which was usually used as a solute in our previous solution growth and was synthesized by conventional arc-melting method from Fe (4N) and Si (5Nup) as a comparison.

Crystal growth of β -FeSi₂ was carried out by the temperature gradient solution growth method using Zn (6N) solvent and the high-purity FeSi₂ or the arc-melted FeSi₂ source. Details of the growth procedure are described in the literatures. Precise growth conditions are listed in Table 1, where T_G and T_S indicate the temperature at growth part and FeSi₂ source part, respectively.

Characterization of the grown crystals was performed by an optical microscope, a scanning electron microscope (SEM) with an energy dispersive X-ray microscopy (EDX) and an X-ray diffraction. The electrical property of the grown crystals was measured by the Hall effect measurement. Impurity concentrations in the crystals were evaluated by the inductively coupled plasma mass spectroscopy (ICP-MS) and secondary ion mass spectroscopy (SIMS) for the mass of grown crystals and each crystal, which was used as the Hall measurement, respectively.

3. Results and discussion

3.1. Synthesize of high-purity FeSi₂ ingot

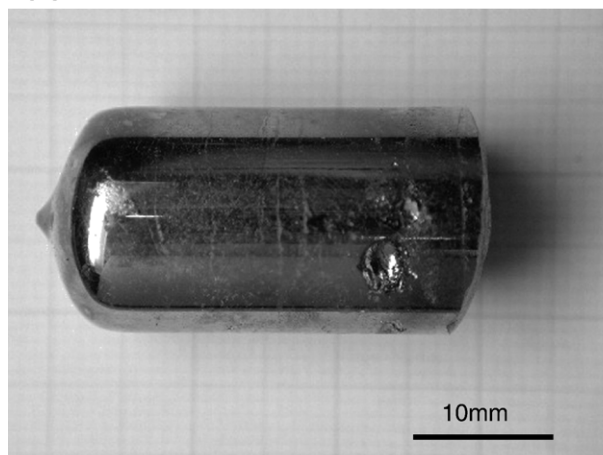
Fig. 1 (a) and (b) show microphotographs of a typical high-purity FeSi₂ alloy ingot synthesized from 5N-Fe and 5Nup-Si by the quartz-ampoule-melting method. The surface on the as-synthesized ingot is a metallic luster. Cross sectional observation revealed that the ingot had no void or crack as shown in Fig. 1 (b). Fig. 2 shows a SEM image on the cross sectional surface of FeSi₂ ingot. The ingot contained only ϵ - and α -phase with their stoichiometric composition. Thus, it is confirmed that the ingot was melted homogeneously. We measured the impurity concentration of the high-purity FeSi₂ ingot and arc-melted FeSi₂ ingot by the GDMS. The results are listed in Table 2. From the table, we found that the concentration of impurities in the high-purity FeSi₂ decreased by one digit or more compared with arc-melted FeSi₂. The total purity of both FeSi₂ ingots was 99.947% for the arc-melted FeSi₂ and 99.997% for the high-purity one. Thus, it is clear that high-purity FeSi₂ source is able to obtain by the quartz-ampoule-melting process. The concentration levels of most of the elements were the same as those in 4N-Fe and 5N-Fe except for

Table 1

Growth conditions of β -FeSi₂ single crystals, The “Q-melt” and “A-melt” mean the quartz-ampoule-melting method and the arc-melting method, respectively

No.	FeSi ₂ source synthesis	(Si/Fe)	T_G [°C]	T_S [°C]	Periods [h]
#1	5N-Fe, Q-melt	1.5	850	905	504
#2	5N-Fe, Q-melt	2.0	870	920	504
#3	5N-Fe, Q-melt	2.5	855	900	504
#4	4N-Fe, A-melt	2.0	885	925	336

(a)



(b)

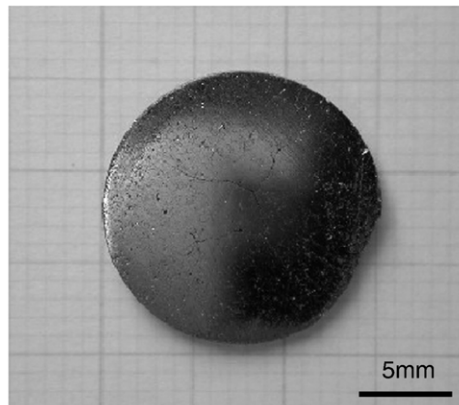


Fig. 1. (a) High-purity FeSi₂ ingot; (b) Cross sectional image of as-polished high-purity FeSi₂ ingot.

W and Cu impurities, i.e., the significant concentration of the elements, such as P, Ni, Al, Cr and Mn in the arc-melted FeSi₂ would be due to the impurity in 4N-Fe source. On the other hand, a large amount of W and Cu impurities was detected in the

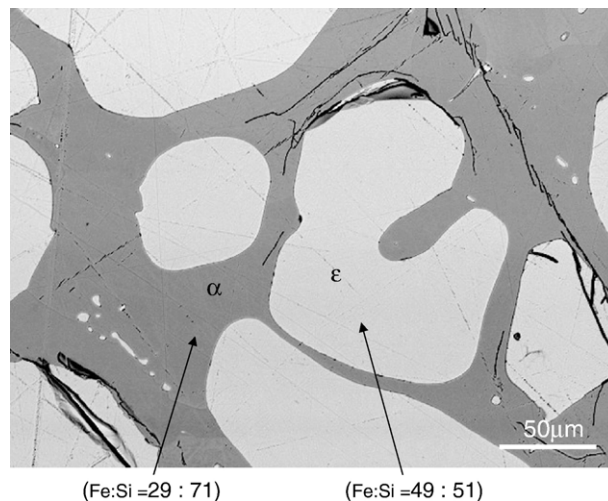


Fig. 2. Cross sectional SEM image of the high-purity FeSi₂ ingot.

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